



VSS ASPHALT TECHNOLOGIES DATA SHEET VER: 1.0 --PRODUCT INFORMATION

DESCRIPTION:

RoadChem™ 105® is a linear SBS triblock copolymer polymer designed to improve the rheological properties of asphalt. It has a wide range of compatibility with different asphalts made from different crudes and using different processing methods.

BENEFITS:

- Linear, pure triblock copolymer
- Contains <1 diblock
- Medium styrene, high modulus copolymer
- Outstanding thermal stability.

PHYSICAL PROPERTIES:

Appearance: Free flowing porous pellet or powder(105P).

Styrene %: 31%

Diblock content: <1%

Density: 0.94 (ASTM D-792)

Tensile strength: 4500psi (ASTM D412)

Hardness Shore A: 78 (ASTM D-2240)

300% modulus: 550psi(ASTM D-412)

Elongation at Break %: 800 (ASTM D-412)

Storage Life: Indefinite in sealed 50 lb bags.

APPLICATION:

Blending: Roadchem™ 105 may be blended using conventional equipment, a high shear mill is required similar to Emultech® PMB blending plants.

TYPICAL FORMULATION: All formulations should be tested in the laboratory before use.

Asphalt should be checked for compatibility by making mixtures in the laboratory. VSS can assist with this process.

A typical formulation for a binder for high deformation resistance will contain 3-5% by weight Roadchem 105® blended with 80/100 pen or other asphalt. (e.g 30/40, 50/70, 180/220 or ANY other Grade)

The mix should be designed in accordance with good practice.

SAFETY:

Roadchem™ 105 is non hazardous. Refer to the MSDS for further information.

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